

Accepted Manuscript

Title: Patterning of diamond like carbon films for sensor applications using silicon containing thermoplastic resist (SiPol) as a hard mask

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PII: S0169-4332(16)31119-9
DOI: <http://dx.doi.org/doi:10.1016/j.apsusc.2016.05.100>
Reference: APSUSC 33293

To appear in: *APSUSC*

Received date: 12-4-2016
Revised date: 18-5-2016
Accepted date: 19-5-2016

Please cite this article as: D.Virganavičius, V.J.Cadarso, R.Kirchner, L.Stankevičius, T.Tamulevičius, S.Tamulevičius, H.Schift, Patterning of diamond like carbon films for sensor applications using silicon containing thermoplastic resist (SiPol) as a hard mask, *Applied Surface Science* <http://dx.doi.org/10.1016/j.apsusc.2016.05.100>

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Patterning of diamond like carbon films for sensor applications using silicon containing thermoplastic resist (SiPol) as a hard mask

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